MEXT (Ministry of Education, Culture, Sports, Science and Technology) Program for Fostering Regional Innovation (Global Type)

-Tokai Region Nanotechnology Manufacturing Cluster-







International Symposium on Advanced Plasma Science and its Applications for Nitrides and **Nanomaterials**

January 28 - February 1, 2013 Nagoya University, Japan

Organizing Committee

Chairperson: Masaru Hori, Plasma Nanotechnology Research Center, Nagoya University Vice-Chairperson: Hideki Masuda, Nagoya Institute of Technology Keiji Nakamura, Chubu University Mineo Hiramatsu, Meijo University

Related Fields

PLASMA SCIENCE

- Plasma Source
- Modeling and Simulation
- Thin Film Deposition Process
- Plasma Biology and Medicine
- Plasma for Nanotechnology
- Advanced Plasma Measuring Technology
- Etching Process
- Flexible Electronics
- Plasma for Clean Energy

NITRIDE SEMICONDUCTORS

- Crystal Growth of GaN and Related Materials
- Characterization
 Device Processing
- MBE Growth of Nitrides
- Optical Devices

Electron Devices **NANOMATERIALS**

- Nanocarbon Materials Porous Materials
- Surface Modification/Surface Functionalization
- Composite/Functionally Grade Materials
- Nanoparticles/Nanowires/Nanorods
- Nanomaterials for Energy Applications

Abstract Submission

Deadline: Tuesday, September 18, 2012 (11:00 am, JST)

JJAP Special Issue

Selected papers will be published in a Special Issue of Jpn. J. Appl. Phys. (JJAP). Instructions for submitting papers will be informed by the end of November.

Award

"ISPlasma2013 Awards" will be given to outstanding papers.

Exhibition

ISPlasma2013 will provide a valuable opportunity for all the related professionals to showcase their technology and products.

Registration Fee

*Refunds for registration or banquet cannot be made at any reason.

Early Registration

General Student JPY 20,000 JPY 3,000

(before December 25, 2012 11:00 am, JST)

Late Registration (until January 17, 2013 11:00 am, JST) JPY 25,000 JPY 5,000

On-Site Registration

JPY 7,000 JPY 30,000

Banquet Fee (on January 30, 2013) JPY 5,000 JPY 2,000

For those attending "Industry-Academia-Government Collaboration Lectures and Panel

Discussion" (Jan. 30) only: Registration Fee is FREE

Sponsored by: Aichi Science & Technology Foundation, ISPlasma2013 Organizing Committee

Co-sponsored: Aichi Prefecture, Nagoya City, Gifu Prefecture, Nagoya University, Nagoya Institute of Technology, Meijo

University, Chubu University, The Japan Society of Applied Physics, The Japan Society of Plasma Science and Nuclear Fusion Research,

The Japanese Association for Crystal Growth

Grants: Support Center for Advanced Telecommunications Technology Research, General Incorporated Foundation, Foun-

dation for Promotion of Material Science and Technology of Japan,

The Murata Science Foundation

Speakers |

Plenary Speaker

Hideo Ohno (Tohoku University, JAPAN)

Keynote Speakers

- S. Fujimura (Tokyo Institute of Technology, JAPAN)
- W. Graham (Queen's University Belfast, UK)
- T. Nozaki (Tokyo Institute of Technology, JAPAN)

Invited Speakers

- P. Chabert (LPP Ecole Polytechnique, FRANCE)
- R. Dwilinski (Ammono Company, POLAND)
- A. Fridman (Drexel University, USA)
- H. Fujioka (Institute of Industrial Science, The University of Tokyo, JAPAN)
- J. G. Han (Sungkyunkwan University, KOREA)
- C. Liu (Tianjin University, CHINA)
- I. Mukhopadhyay (Pandit Deendayal Petroleum University, INDIA)
- M. Nakayama (Nagoya Institute of Technology, JAPAN)
- P. Ruterana (CIMAP, UMR 6252, CNRS, ENSICAEN, CEA, FRANCE)
- M. Van de Sanden (Dutch Institute for Fundamental Energy Research, THE NETHERLANDS)
- W. Walukiewicz (Lawrence Berkeley National Laboratory, USA)
- T. Wei (Chung-Yuan University, TAIWAN)
- S. Yamasaki (AIST, JAPAN)

Tutorial Speakers

- J. Duboz (CRHEA-CNRS, FRANCE)
- F. Fracassi (University of Bari, ITALY)
- Y. Nanishi (Ritsumeikan University, JAPAN/Seoul National University, KOREA)
- K. Sasaki (Hokkaido University, JAPAN)

Focused Sessions

- Energy Revolution
- Advanced Nitride Semiconductors
- Advanced Carbon Materials
 - Industry-Academia-Government Collaboration

Panel Discussion

Toward the Establishment of Global Innovation Research Cluster (Jan. 30) < Moderator > S. Fujimura (Tokyo Institute of Technology, JAPAN)

Perspective of Nitride Semiconductors

-The Role of Plasma Science and Nano Technology- (Jan. 31)

< Moderator > O. Oda (Nagoya Institute of Technology, JAPAN)

Towards Smart Energy Cities (Feb. 1)

<Moderator> T. Nozaki (Tokyo Institute of Technology, JAPAN)

*Listed in alphabetical order. *Program and speakers listed above may change.

Contact Us

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